Opportunities in vertexing and tracking

Jens Dopke, Laura Gonella UK meeting on future e+e- Higgs/EW/top/... Factory Oxford, 5 July 2022

Outline

- Tracking and vertex requirements for future e+e- colliders
- Existing detector concepts
- Technology roadmap
- Discussion on opportunities for the UK

Future e⁺e⁻ colliders

Requirements for Vertex and Tracking Dete

https://cds.cern.ch/record/2784893

CLIC concept

ILC concepts

ILD

ILC concepts FCC-ee concepts

- Large-volume solenoid, enclosing calorimeters and tracking.
	- Only exception IDEA concept.
	- Smaller B-field, larger tracker outer radius at FCC-ee to retain momentum resolution.
- Highest precision, lowest mass, smaller radius vertex detector.
	- Silicon pixel detectors (MAPS, hybrids).

- Large area, low mass tracking detector.
	- Cost and ease of construction are key drivers for technological development.
	- All silicon (pixel/strip detectors) or silicon + gaseous detectors (TPC, drift chamber).
	- Gas detectors provide low mass, low cost large lever arm coverage with added PID.

- Bunch trains (linear) vs. continuous beam (circular).
	- Power pulsing of FE electronics at linear colliders, no need for active cooling (i.e. air cooling can be used) \rightarrow reduced material.
	- Bunch spacing down to 20 ns at FCC-ee, active cooling required \rightarrow challenging to meet power management within low mass requirements, cooling studies for low mass, new technology nodes for low power electronics.

- Beam-induced backgrounds more challenging at linear colliders.
	- CLIC 3TeV worse case: largest vertex detector inner radius; up to 8.8 hits/mm2/train; 0.5 ns bunch spacing results in out-of-time pile-up, ns-level timing needed.
- Extremely high luminosities at FCC-ee (Z pole).
	- High statistical precision requires control of systematics down to 10^{-5} level \rightarrow significant implications for the design of a stable and lightweight mechanical support.

Technology development ACHUOLOGUL QAVALODME recinionogy acychoping by the LHCb Upgrade II relies on an ecient and precise vertex detector with real time ACDOOLOGU DAVALODME recinion y geven princ by the LHCb Upgrade II relies on an ecient and precise vertex detector with real time

- The existing vertex and tracking detector concepts are based on R prototype technologies (or extrapolations from state-of-the-art detectors) pected in future running will also demand increased detector granularity for the LHCb riototype technologies (or extrapolatio which also would highly benefits from having 4D-tracking. The higher occupancy experted in future running will also detect in function α \overline{r} rototype technologies (or extrapolation
- Many years of development of detector technologies for e+e- colliders provide solutions that meet some but not all key requirements. plany years of development of detector NA62, which will occur during this decade. Devices with *O*(10 ps) timing resolution will t_0 to access goals of Heavy Ion experiments, such as ALICE, and those α -inany years of development of detector provide colutions that most some but NA62, which will during this decade. Devices with*O*(10 ps) timing resolution will
- R&D (following the ECFA roadmap) is needed to meet all requirem to further improve performance. ONE (TONOWING THE ECTA FORUMAL) IS H to further improve performance. \overline{a} $DOP/4$ ω D (fundwing the ECFA fuadmap) is n $t_{\rm c}$ for the assumentation is as the very as those required for ϵ to further improve performance. 3D-stacking is the analysis of the analysis to the analysis of the analysis to
- For solid state detectors: FUE SUIIU STATE CRIECTORS. F_{α} α solid state detectors α TUE SUIIU STATE ACTECTORS.

DRDT 3.1 - Achieve full integration of sensing and microelectronics in mono-DRDT 3.1 - Achieve full integration of sensing and microelectronics in monolithic CMOS pixel sensors. lithic CMOS pixel sensors.

Developments of Monolithic Active Pixel Sensors (MAPS) should achieve very high spa-Developments of Monolithic Active Pixel Sensors (MAPS) should achieve very high spatial resolution and very low mass, aiming to also perform in high fluence environments. tial resolution and very low mass, aiming to also perform in high fluence environments. To achieve low mass in vertex and tracking detectors, thin and large area sensors will To achieve low mass in vertex tracking detectors, thin and large area sensors will be crucial. For tracking and calorimetry applications MAPS arrays of very large areas, be crucial. For tracking and calorimetry applications MAPS arrays of very large areas, but reduced granularity, are required for which cost and power aspects are critical R&D but reduced granularity, are required for which cost and power aspects are critical R&D drivers. Passive CMOS designs are to be explored, as a complement to standard sensors drivers. Passive CMOS designs are to be explored, as a complement to standard sensors fabricated in dedicated clean room facilities, towards hybrid detector modules where the sensors is bonded to an independent ASIC circuit. Passive CMOS sensors are good the sensors is bonded to an independent ASIC circuit. Passive CMOS sensors are good candidates for calorimetry applications where position precision and lightness are not candidates for calorimetry applications where position precision and lightness are not major constraints (see Chapter 6). State-of-the-art commercial CMOS imaging sensor (CIS) technology should be explored for suitability in tracking and vertex detectors.

DRDT 3.2 - Develop solid state sensors with 4D-capabilities for tracking and DRDT 3.2 - Develop solid state sensors with 4D-capabilities for tracking and calorimetry. calorimetry.

Understanding of the ultimate limit of precision timing in sensors, with and without Understanding of the ultimate limit of precision timing in sensors, with and without internal multiplication, requires extensive research together with the developments to internal multiplication, requires extensive research together with the developments to increase radiation tolerance and achieve 100%-fill factors. New semiconductor and tech-increase radiation tolerance and achieve 100%-fill factors. New semiconductor and technology processes with faster signal development and low noise readout properties should nology processes with faster signal development and low noise readout properties should also be investigated. also be investigated.

https://cds.cern.ch/record/2

DRDT 3.3 - Extend capabilities of solid state sensors t_0 fluences. fluences.

To evolve the design of solid state sensors to cope with $\frac{1}{\sqrt{2}}$ is essences it is essential to measure the properties of silicon and α 1×10^{16} n_{eq} cm⁻² to 5×10^{18} n_{eq} cm⁻² and to develop simulation m ingly include results from microscopic \sim \sim \sim ats of point technologies will need improved radiation to the for use at function to the tolerance for use at function \mathbf{C} periments. Exploration of alternative semiconductors and 2D-materials showledge should be shown as \mathcal{S} start, having as a target full \bigcirc \bigcirc if it even after the extreme innermost parts of the Δ Δ a specific concern to be addressed in activation of all the components in the detector. Exploration is semiconductors and $\frac{1}{2}$ derials to further push radiation tolerance. ingly include results from microscopic $\{Q\}$ of point technologies will need improved radiation to the for use at function to the set of use at function \mathbf{C} periments. Exploration of alternative semiconductors and 2D-materials showledge should all start, having as a target full \sim \sim \sim \sim \sim even after the extreme innermost parts of the $d \times \sqrt{d}$ specific concern to be addressed in activation of all the \sim $\mathbb{R}^{\mathbf{0}}$ in the detector. Exploration is But the sensor of silicon and to the sensor of silicon and to the relation of alternative and to the conductors are for use of alternative and the form of \mathbb{R} and \mathbb{R} and \mathbb{R} and \mathbb{R} and \mathbb{R} and $\$

DRDT 3.4 - Develop full 3D-interconnection technolog vices in particle physics. vices in particle physics.

3D-interconnection is commercially used, for instance in imaging sensors, the use of use the use of use the use of use of use of use o most appropriate technology process for the different functionalities of the devices. For the devices of the devices of the devices. For the devices of the device particle physics detectors, this process would allow more comp with minimal power consumption. This approach also provides of finer feature sizes to enable lower pitch and new digital features. effort towards building a demonstrator as a starting cornerstor demonstrator programme should be established to develop suitable silicon sensors, cost established to develop suit effective and reliable chip-to-wafer and/or wafer-to-wafer bond use these to build multi-layer prototypes with vertically stacking layers of electronics, α interconnected by through-silicon vias $(TSVs)$ and integrating s ities. ities.

Technology impact on physics programme

Figure 3.1: Schematic timeline of categories of experiments employing solid state sensors together with DRDTs and R&D tasks. The colour coding is linked not to the intensity of the required effort but to the potential impact on the physics programme of the experiment: Must happen or main physics goals cannot be met (red, largest dot); Im-
portant to meet several physics goals (orange, large dot); Desirable to enhance physics
reach (yellow, medium dot); R&D needs being met (g portant to meet several physics goals (orange, large dot); Desirable to enhance physics reach (yellow, medium dot); R&D needs being met (green, small dot); No further R&D required or not applicable (blank).

Low X/X_o

Low power

High rates

Low X/X_o

Low power

High rates

Vertex detector²⁾

Tracker⁵⁾

Emerging/future technologies

Smaller feature size technologies to further improve

Silicon detector technologies

 COL cmos to allow for functions inside the pixel cell as COL cell as COL SOI, 3D integration,

Sonsaitively seupled devises. CCD (various types): Ultimate processitively capacitively coupled devices. LEE warrous types). Oftime

DRDT 3.1 - Monolithic CMOS

- Monolithic Active Pixel Sensors (MAPS) in commercial CMOS imaging technology could provide solutions for both vertex and tracking layers at e+e- colliders.
	- High granularity and low power consumption demonstrated by state-of-the art, further improved by the use of smaller technology nodes (see next slide).
	- Low cost, large volume production and ease of assembly would favour use in trackers wrt. strips.
		- Tracking detectors is an area where there is a lot of UK expertise.
		- Also consider overlapping requirements with calorimeters, and UK work on that \rightarrow possible synergies?

J. Phys. G: Nucl. Part. Phys. **41** (2014) 087002 The ALICE Collaboration ALPIDE @ ALICE ITS2 Example state-of-the-art MAPS detector

Layer 2

Layer 2

 Layer 1 Rmid 31,50

Layer 1

2,13

Rmid 245,45

Rmid 245,45

Layer 4

Layer 4

10m2 surface Inner Barrel = 0.3% X/X0 per layer Outer Barrel = 0.8% X/X0 per layer 50 kHz interaction rate (Pb-Pb) 400 kHz interaction rate (pp)

Layer 5

Layer 5

Rmax 345,40 Rmid 343,85

Rmax 345,40 Rmid 343,85

180 nm CMOS TowerJazz $27 \times 29 \mu m^2$ pixel pitch 5 μs integration time 40 mW/cm^2 (Sec. 2.4). It will be shown that the state-of-the-art MAPS do not fulfil the ALICE its $\frac{1}{1}$

Stitched wafer scale sensors for cylindrical layers

- Exploration of 65 nm CMOS imaging processes for MAPS driven by CERN EP R&D WP1.2 and ALICE ITS3 upgrade.
	- 12" wafers, higher logic density, smaller pixels, faster read-out, lower power consumption.
- Wafer-scale, low power sensor design for truly cylindrical minimal material budget layers → New technology node & new detector concept
	- Mechanical support, power distribution and data lines outside acceptance, air cooling. MLR1 submission

DRDT 3.4 - 3D integration

- Industrial developments of heterogeneous integration technologies to achieve further reductions in cost and power.
- 3D stacking is being studied for future HEP applications \rightarrow potential for increased functionality and performance of silicon trackers.
- Pursuing this path would require large scale of investment and establishing a privileged relation with industrial partner(s), but it is a field where there isn't a clear leadership now.
	- Dependent on availability of process for R&D.
- There is expertise in the UK to work on each layer in the stack and on the interconnection technologies.

Electronics (beyond sensors) (Chapter 7)

(See Figure 7.1, R&D Roadmap for an overview)

- Under DRDT 7.2: High-granularity pixel readout chip with 10–100ps timing and charge measurement capability in 28nm CMOS, and highly programmable features
	- An opportunity to hang on to our involvement from RD53? A lot of this is chip design in IP blocks that can be useful elsewhere, but do we think it's worth the investment?
- DRDT 7.5 Evaluate and adapt to emerging electronics and data processing technologies
	- Silicon photonics as the successor to actively modulated VCSEL-based links, facilitating fullcustom photonic integrated circuits (PICs) for HEP
		- So far as I am aware this could be a wide open field with possible contributions from the UK - can significantly reduce optics power, expertise doesn't exist, but not sure it does elsewhere?
	- 3D integration and high density interconnects
		- We already have people working on some of these
- Under DRDT 7.1: Power and readout efficiency:
	- High conversion factor DC-DC converters based on new processes and materials, and associated power management circuit blocks
		- Long history of testing powering schemes, GaN HV switches fully developed through the UK now being looked at for higher efficiency DCDC at CERN

Mechanics & cooling (Chapter 8)

(Have a look at Figure 8.1)

- DRDT 8.1 Develop novel magnet systems
- DRDT 8.2 Develop improved technologies and systems for cooling
	- Experience with microchannel cooling, but are we happy? Other approaches?
- DRDT 8.3 Adapt novel materials to achieve ultralight, stable and high precision mechanical structures. Develop Machine Detector Interfaces
	- Lots of carbon fibre experience in the UK, but lack of industry backing can be a problem
	- Work on detectors without support structures ongoing…

Working with UK industry

- Developments that involve UK industrial partners would be beneficial for funding situation.
- Involvement of existing infrastructure for large scale assembly also to be considered (for example national labs/SRF).
- Some examples of UK company for sensor production and interconnections: Alter Technology, Custom Interconnect Ltd, ElementSix, Micron, Micross, Nordson, Te2v.
	- There is certainly more.
- We are already working with some of these industrial partners.
	- Interest from some of these companies to work with us but small-ish R&D budgets and long development cycles not attractive for their business model.

Opportunities for the UK - Thoughts for discussion

- The UK community interested in e+e- colliders should identify opportunities where it can engage with the international efforts in a leading role.
- There is a large community in the UK working on many aspects of vertex and tracking detectors development, construction and operation (sensors, ASICs, mechanics, readout, cooling, DAQ, ...) \rightarrow a lot of expertise.
- At this early stage it would be good to identify technologies that are agnostic to the specific collider implementation, rather then splitting the community (and the resources) into groups working on detector R&D for different e+e- collider.
- The community should aim at a unified and coordinated vision.
	- Devise a common generic R&D programme that then can branch off for specific/targeted implementations required by different facilities.
- What we really need is a Workshop on Tracking and Vertexing for e+ecolliders, where the UK community comes together, presents their developments and identifies strengths that can culminate in a funded route for development and ultimately leadership in a section of the field.
	- What developments/expertise/links with industry can we leverage on?

Backup

